

Fig. 1D Fig. 1E Fig. 1A Fig. 1C Fig. 1B HIGH FREQUENCY POWER 19 02 GAS (PIPES 2, 5) SMALL QUANTITY SiH₄ GAS (PIPE 1) Ar GAS (PIPES 3, 6) LARGE QUANTITY SiH₄ GAS (PIPE 4)

Inventor: Shigeo ISHIKAWA Application No.: 09/832,093 Group Art Unit: 2823 Title: Film Forming Method in which Flow Rate